

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No. .... Unknown  
Filing Date ..... Filed Herewith  
Inventor ..... Weimin Li et al.  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... Unknown  
Examiner ..... Unknown  
Attorney Docket No. .... MI22-2274  
Customer No. .... 021567  
Title: Methods of Depositing Silicon Dioxide Comprising Layers in the Fabrication of Integrated Circuitry, Methods of Forming Trench Isolation, and Methods of Forming Arrays of Memory Cells

**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

References -- See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. Pursuant to 1276 OG 55, August 5, 2003, no copies of cited U.S. patents or U.S. patent application publications are included, as the date of filing of this patent application occurs after June 30, 2003. No admission is made regarding whether all the listed references are prior art.

Respectfully submitted,

Dated: 3-22-04By:   
Mark S. Matkin  
Reg. No. 32,268

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2274	SERIAL NO. Unknown		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Weimin Michael Li et al.			
				FILING DATE Filed Herewith	GROUP Unknown		
<b>U.S. PATENT DOCUMENTS</b>							
*Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,300,219 B1	10/09/01	Doan et al.			
	AB	6,534,395 B2	03/18/03	Werkhoven et al.			
	AC	10/615,051		Vaartstra (as filed)			07/07/2003
	AD	10/655,699		Derderian et al. (as filed)			09/05/2003
	AE						
	AF						
	AG						
	AH						
	AI						
<b>FOREIGN PATENT DOCUMENTS</b>							
		Document Number	Date	Country	Class	SubclasS	Translation
	AJ	WO 02/27063 A2	04.04.02	WIPO (Harward College)			Yes      No
	AK						
	AL						
<b>OTHER REFERENCES</b> (including Author, Title, Date, Pertinent Pages, Etc.)							
	AM		Hausmann et al., <i>Rapid Vapor Deposition of Highly Conformal Silica Nanolaminates</i> , 298 SCIENCE 402-406 (October 11, 2002)				
	AN		Klaus et al., <i>Atomic Layer Deposition of SiO<sub>2</sub> Using Catalyzed and Uncatalyzed Self-Limiting Surface Reactions</i> , 6 SURFACE REVIEW AND LETTERS, Nos. 3 and 4, pp. 435-448 (1999).				
	AO		Miller et al., <i>Self-limiting chemical vapor deposition of an ultra-thin silicon oxide film using tri-(tert-butoxy) Silanol</i> , 397 THIN SOLID FILMS 78-82 (2001).				
EXAMINER		DATE CONSIDERED					
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-2274	SERIAL NO. Unknown		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT: Weimin Michael Li et al..			
					FILING DATE Filed Herewith		GROUP Unknown	
<b>U.S. PATENT DOCUMENTS</b>								
*Examiner's Initials		Document Number	Date	Name		Class	Subclass	Filing Date If Appropriate
	AA							
	AB							
	AC							
	AD							
	AE							
	AF							
	AG							
	AH							
	AI							
<b>FOREIGN PATENT DOCUMENTS</b>								
		Document Number	Date	Country	Class	Subclass	Translation	
	AJ						Yes	No
	AK							
	AL							
<b>OTHER REFERENCES</b> (including Author, Title, Date, Pertinent Pages, Etc.)								
	AM		Hausmann et al., "Catalytic vapor deposition of highly conformal silica nanolaminates", Department of					
			Chemistry and Chemical Biology, Harvard University, May 14, 2002, pp. 1-13.					
	AN							
	AO							
EXAMINER		DATE CONSIDERED						
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								